# **Back-Illuminated Non-Isolated Single-Photon Avalanche Diode** in Foundry CMOS Technology

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## **SPAD** Applications

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#### Results



600

### Conclusion

 The proposed BI non-isolated SPAD with backside patterning achieves a ~50% higher PDP at 940nm than

the default SPAD while it shows a comparable DCR.

- The PDP will be improved by increasing the thickness of the P-Epi.
- It is expected to play an important role in biomedical and LiDAR applications.

#### 700 800 900 Wavelength (nm) Performance summary w/o BSP w/BSP Active area 10µm Breakdown voltage **30V Excess voltage 3V** DCR (cps / µm<sup>2</sup>) 0.34 0.64 **940nm PDP** 10.7% 16%